

Abstract of Disclosure

SEMICONDUCTOR PROCESSING APPARATUS

A semiconductor processing apparatus includes a wafer supporting unit for supporting a wafer and a wafer holder positioned outside of the wafer supporting unit. The wafer holder further includes a plurality of horizontal parts extending axially around the wafer supporting unit and a plurality of vertical parts vertically extending from the horizontal parts respectively. Topmost surfaces of the vertical parts and a topmost surface of the wafer supporting unit are non-coplanar.

Figure 1